

10  
AUG 11 1997



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Mark D. Owen, Bonnie A. Larson,  
and Jozef Van Puymbroeck

Group Art Unit: 2106

Application No. 08/651,036

Filed: May 17, 1996

For: **METHOD EMPLOYING UV LASER PULSES OF VARIED ENERGY DENSITY TO FORM DEPTHWISE SELF-LIMITING BLIND VIAS IN MULTILAYERED TARGETS**

Date: August 5, 1997

Examiner: Gregory Mills

AMENDMENT

TO THE ASSISTANT  
COMMISSIONER FOR PATENTS:

In response to the April 9, 1997 Office action, please amend the above-identified patent application as follows.

In the Drawings:

Figs. 4 and 6 replace the originally filed Figs. 4 and 6.

In the Specification:

Page 1, line 18, after "1994" insert--, now U.S. Patent No.  
5,593,606--

Page 16, line 14, change "but below" to --but above--.

In the Claims:

Amend claims 1 and 2 as follows:

1. (Amended) A method for laser machining a depthwise self-limiting blind via in a multilayered target including at least first and second conductor layers having respective first and second conductor ablation energy thresholds and a dielectric layer having surfaces and a dielectric

08/27/1997 SCARMICH 000001510652 Energy threshold, the first and second conductor layers positioned  
01 FC:103 176.00 DP above and below, respectively, the surfaces of the dielectric layer and the